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Zhaoying Zhou

Toshio Fukuda

Helmut Seidel

Xinxin Li

Haixia Zhang

Tianhong Cui

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Contents

v	<i>Symposium Committees</i>
vii	<i>Conference Committee</i>
ix	<i>Introduction</i>

SESSION 1

7510 02	Tunable RF MEMS capacitor for wireless communication [7510-34] X. Li, Beijing Jiaotong Univ. (China); Y. Xia, J. Liu, Peking Univ. (China); L. Yin, Beijing Jiaotong Univ. (China); Y. Liu, D. Fang, H. Zhang, Peking Univ. (China)
7510 03	Mechanical design and system-level analysis of a novel micromirror array [7510-20] Q. Sun, Univ. of British Columbia (Canada) and National Univ. of Defense Technology (China); M. Cai, N. Wang, E. Cretu, Univ. of British Columbia (Canada)
7510 04	Out-of-plane vibration measuring technique based on dynamic AFM [7510-01] L. Xu, L. Ma, X. Fu, X. Hu, Tianjin Univ. (China)
7510 05	A simulation of dielectrophoresis force actuated liquid lens [7510-08] X. Yao, J. Xia, Southeast Univ. (China)
7510 06	Detection system of capillary array electrophoresis microchip based on optical fiber [7510-16] X. Yang, H. Bai, W. Yan, Dalian Univ. of Technology (China)

SESSION 2

7510 07	A novel evaluating method for the MEMS-based uncooled IR system [7510-04] B. Fan, Y. Zhao, L. Dong, Beijing Institute of Technology (China)
7510 08	Optimal algorithm to improve the calculation accuracy of energy deposition for betavoltaic MEMS batteries design [7510-24] S. Li, Beijing Institute of Technology (China) and China Academy of Space Technology (China); H. Chen, M. Sun, Beijing Institute of Technology (China); Z. Cheng, Xiamen Univ. (China)
7510 09	Analysis of cylindrical subwavelength diffractive optical elements by an approximate vectorial diffraction method [7510-21] J.-S. Ye, Y. Zhang, Capital Normal Univ. (China)

POSTER SESSION

7510 0A	Study on electroforming Ni-Fe alloy microstructure [7510-03] X. Zheng, Y. Liu, F. Gu, Huaiyin Institute of Technology (China)
---------	---

- 7510 0B **Study of SiN_x thin film character with gas flow rate in PECVD** [7510-05]
Z. Kang, W. Li, Y. Jiang, Univ. of Electronic Science and Technology of China (China)
- 7510 0C **The real-time infrared image denoising method of double buffering for microcantilever-based infrared imaging system** [7510-06]
C. Gong, M. Hui, L. Dong, Y. Zhao, Beijing Institute of Technology (China)
- 7510 0D **Reactive Ion Etching of Al-1%Cu alloy thin films** [7510-09]
J. Gou, Z. Wu, H. Tai, K. Yuan, Univ. of Electronic Science and Technology of China (China)
- 7510 0E **Design and simulation of tunable micromirror for two-color microbolometer** [7510-10]
Y. Gong, W. Li, H. Cai, Z. Li, C. Chen, Y. Jiang, Univ. of Electronic Science and Technology of China (China)
- 7510 0F **Simulation and optimal design for deformable mirror supporting structure** [7510-13]
F. Zhao, Beijing Technology and Business Univ. (China); P. Wang, Beijing Institute of Technology (China); Y. Gong, J. Lin, H. Xiang, Beijing Technology and Business Univ. (China)
- 7510 0G **Influence of PECVD process parameters on the etching of SiN_x films** [7510-17]
J. Gou, Z. Wu, H. Tai, K. Yuan, Univ. of Electronic Science and Technology of China (China)
- 7510 0H **An analysis on the urban spatial expansion of Hangzhou based on remote sensing** [7510-18]
Q. Chen, J. Zhou, C. Huang, K. Li, Zhejiang Univ. of Technology (China)
- 7510 0I **Effect of different support structures on the characteristic of the grating light modulators** [7510-26]
W. Wei, W. Chen, Y. Zhu, N. Wang, Key Lab. of Opto-electronic Technology and Systems (China) and Chongqing Univ. (China); Y. Qin, Chongqing Univ. (China); J. Zhang, Key Lab. of Opto-electronic Technology and Systems (China) and Chongqing Univ. (China)
- 7510 0J **Kernel regression image processing method for optical readout MEMS based uncooled IRFPA** [7510-27]
L. Dong, X. Liu, Y. Zhao, M. Hui, X. Zhou, Beijing Institute of Technology (China)
- 7510 0K **1-dimension nano-material-based flexible device** [7510-30]
X. Yang, Tsinghua Univ. (China) and State Key Lab. of Transducer Technology (China); Z. Zhou, F. Zheng, Tsinghua Univ. (China)
- 7510 0L **Analysis and modeling of thermal failure based on a MEMS thermally driven structure** [7510-35]
X. Li, Beijing Jiaotong Univ. (China); Q. Yuan, L. Lang, J. Liu, Y. Liu, D. Fang, H. Zhang, Peking Univ. (China)
- 7510 0M **Design and characterization of a gas actuated pump for μ TAS** [7510-36]
X. Li, Peking Univ. (China) and Beijing Jiaotong Univ. (China); X. Yu, Peking Univ. (China)

Author Index

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Introduction

These proceedings result from the 2009 International Conference on Optical Instrument and Technology (OIT'09), held in Shanghai, China, 19–21 October 2009. The conference was the second event following the success of OIT'08 and it was sponsored and supported by SPIE, China Instrument and Control Society (CIS), and the Chinese Optical Society (COS).

OIT'09 was a professional conference which was combined with the exhibition of The 20th Fair for Measurement Instrumentation and Automation (MICONEX).

OIT'09 focused on instrument science and related technology involved in many technical aspects such as detection; observation; information collection, transfer and storage; communication; economization on energy; environmental protection; inspection and prevention of food security, traffic safety and mine safety; measure and control for aviation and space engineering, etc.

These proceedings, a collection of eight volumes, contain the accepted oral and poster papers presented at OIT'09. It is truly a great pleasure for me that the most recent progress in optical instrumentation technology is reported in the OIT'09 proceedings. I firmly believe that the papers included in these volumes will provide reference information in up-to-date techniques of optical instrumentation technology.

The OIT'09 conference collected over 630 papers from different countries or regions of the world. Over 400 authors came from more than 14 countries, including Canada, Iran, Japan, Russia, Singapore, USA, Sweden, Switzerland, Pakistan, the Netherlands, Republic of Korea, Slovenia, Germany and China. Published in these eight volumes of the Proceedings of SPIE are close to 455 papers. The technical fields of the presented papers at the conference cover a lot of current advanced technologies. The cutting-edge technologies and applications of optical instruments are discussed. Quite a few invited papers describe exciting achievements in the fields of optical instrument technology. It is evident that the OIT'09 conference has provided an excellent platform for participants and colleagues in research and development to share the technical progress and to develop new partnerships or broaden new markets.

SPIE has given great support to organize this international conference by collaborating with us in the whole organizing process from paper collection to the proceedings publication. COS has provided enough support and assistance.

Finally, on behalf of CIS and conference general chairs, I would like to heartily thank our supporters and committee members for all they have done for this conference. Thanks also go to all authors for their contributions; to all of the

participants and friends for their interest, especially those who have traveled great distances and taken time from their busy schedules to attend the conference. Thanks also go to the staff of COS for their support. I am also grateful to the SPIE staff for their support and collaboration in publishing these eight volumes.

Songlin Zhuang

Chairman, China Instrument and Control Society (CIS)